



Thermal performance investigation of DQW GaInNAs laser diodes

Jun Jun Lim, Roderick MacKenzie, Slawomir Sujecki, Eric Larkins

*Photonic and Radio Frequency Engineering Group, School of Electrical and Electronic Engineering
University of Nottingham, Nottingham NG7 2RD*

M. Sadeghi, S.M. Wang, G. Adolfsson, Y.Q. Wei, A. Larsson

Photonics Laboratory, Chalmers University of Technology, SE-41296 Göteborg, Sweden

P. Melanen, P. Uusimaa

Modulight Inc., Hermiankatu 22, FIN-33720 Tampere, Finland

A.A. George, P.M. Smowton

*Cardiff School of Physics and Astronomy,
Cardiff University, Queens Buildings, The Parade, Cardiff, CF24 3AA*

Acknowledgements

We gratefully acknowledge the support of the European Commission through the FP6 IST project **FAST ACCESS** (IST-004772)



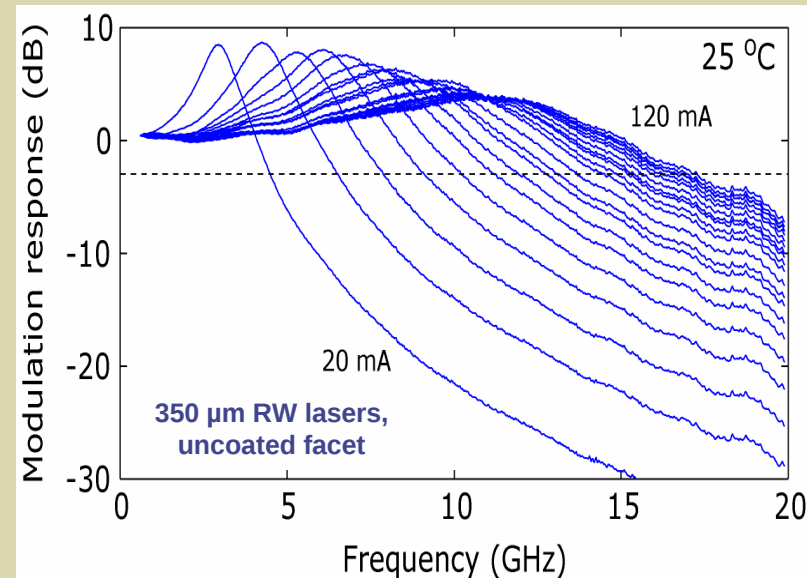
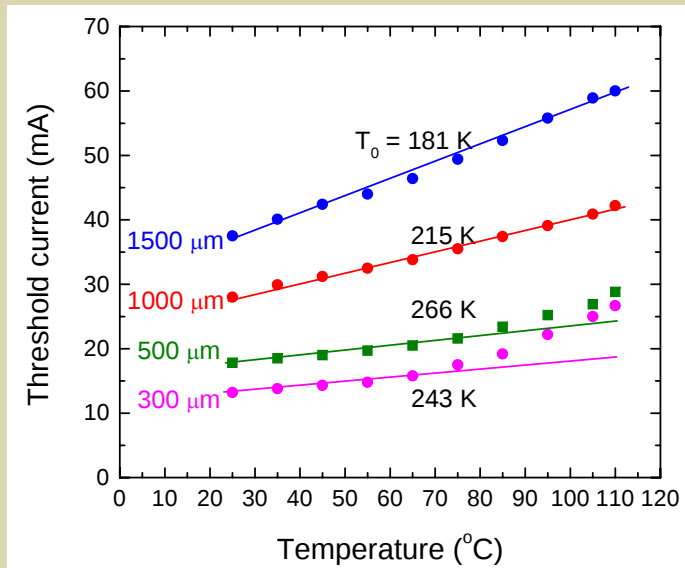
Presentation Outline



The University of
Nottingham

- 1. Introduction**
- 2. Device structure**
- 3. Calibration of gain data**
- 4. Description of laser simulator**
- 5. Calibration of operating characteristic**
- 6. Cladding doping concentration investigation**
- 7. Conclusion**

Dilute Nitride Lasers

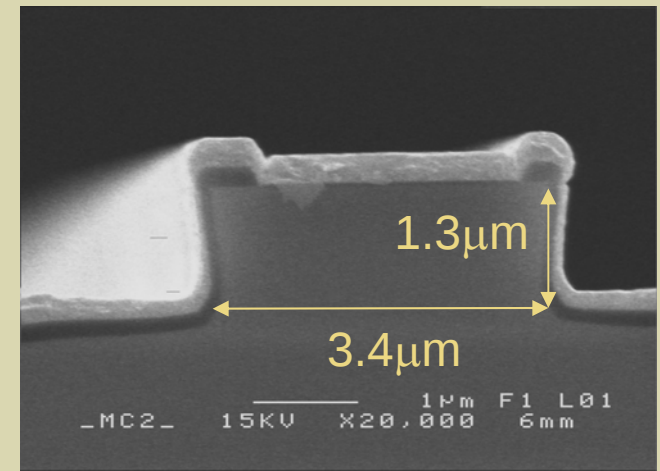
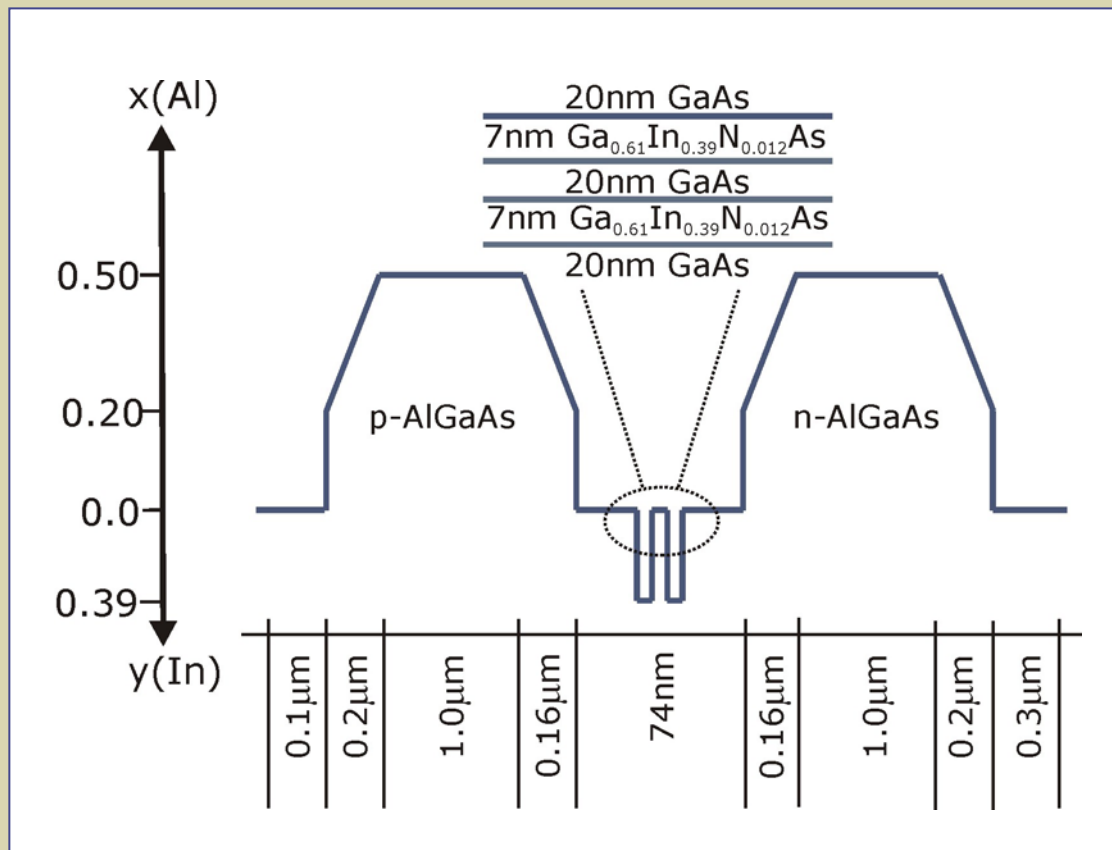


- ◆ Bandgap energy reduction – Longer wavelength
- ◆ Large conduction band offset – High T_0
- ◆ Low-cost alternative to InP lasers for access networks
- ◆ 17 GHz maximum modulation bandwidth
- ◆ Characteristic temperature, $T_0 = 181\text{-}266\text{ K}$ (20-70°C)

Reference: Y.Q. Wei et al., *Optics Express*, Vol. 14, pp. 2753-2759, 2006

Dilute Nitride Laser Structure

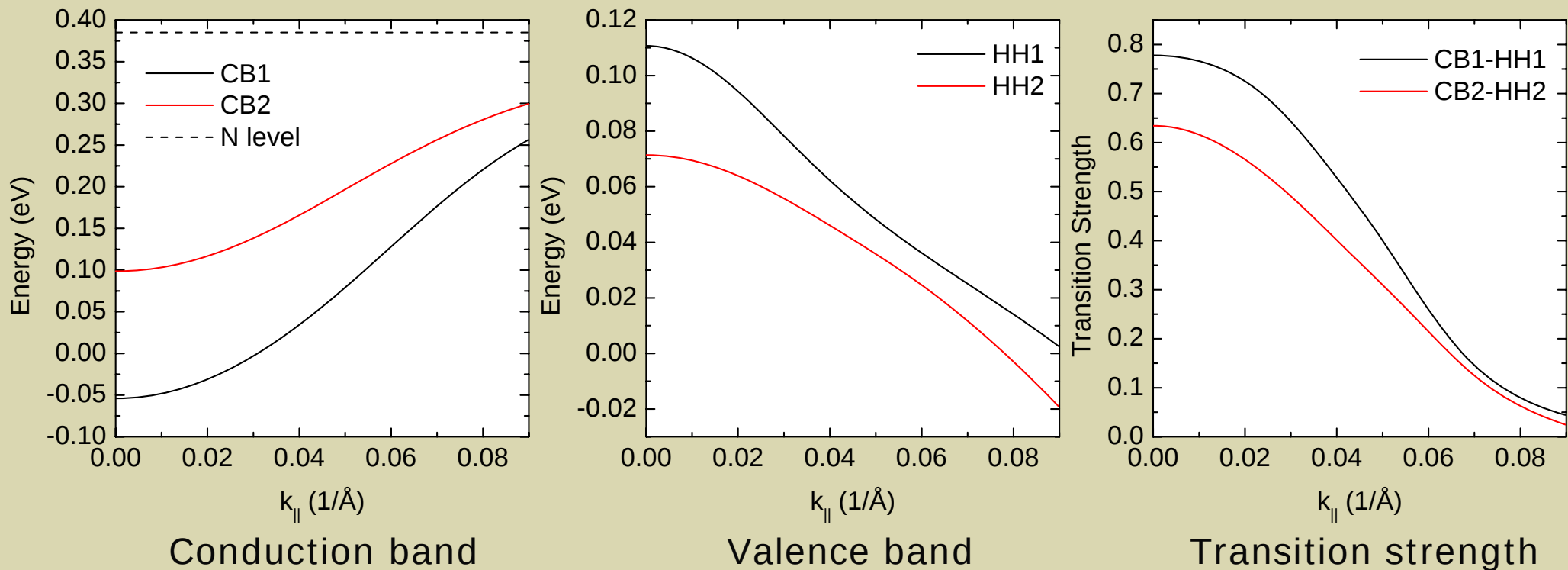
- ◆ 7nm $\text{Ga}_{0.61}\text{In}_{0.39}\text{N}_{0.012}\text{As}$ /GaAs DQW grown by Chalmers University
- ◆ Ridge width of $3.4\mu\text{m}$, and etch depth of $\sim 1.3\mu\text{m}$ processed by Modulight Inc.



Reference: Y.Q. Wei et al., *Appl. Phys. Lett.*, Vol. 88, 051103, 2006.

Bandstructure Calculation

- ◆ BAC conduction band model
- ◆ Use 4x4 $\mathbf{k} \cdot \mathbf{p}$ valence band mixing model
- ◆ Material parameters from: Vurgaftman & Meyer, JAP **89**, 5815, 2001
- ◆ Band-offset ratio $\Delta E_c / \Delta E_g = 0.70$
- ◆ Nitrogen level relative to VBM of GaAs, $E_N = 1.65$ eV
- ◆ Adjusted interaction parameter, $V_{MN} = 2.15 \sqrt{x}$

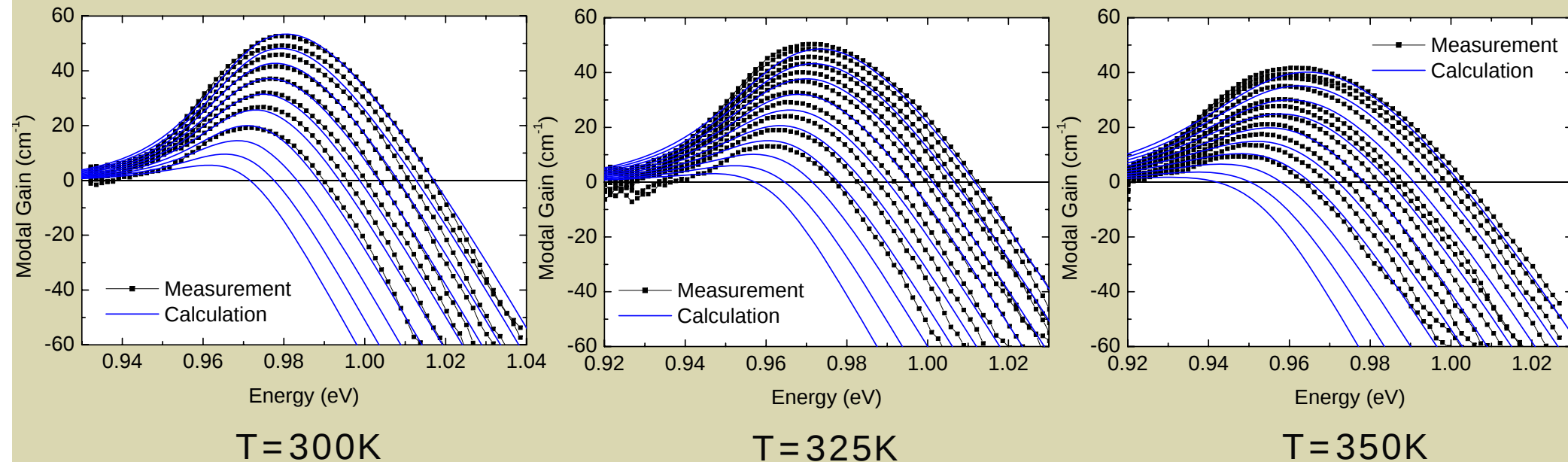


Calibration of Gain Spectra

- ◆ Experimental gain measured using the segmented contact method
- ◆ Theoretical gain transformed from spontaneous emission spectra

$$g(E) = \frac{3\pi^2 \hbar^3 c^2}{2n^2 E^2} R_{\text{spont}}(E) \left[1 - \exp\left(\frac{E - \Delta E_F}{kT}\right) \right]$$

- ◆ Spontaneous emission spectra broadened using hyperbolic secant function
- ◆ Broadening lifetime: $\tau_{in} = (1.95 \times 10^{-13} - 4 \times 10^{-16} T) \cdot (n/10^{18})^{-1/2} \text{ s}$



Description of 2D Laser Simulator



- ◆ The model solves the following equations:

Poisson's Equation

$$\nabla \cdot (\epsilon_r \epsilon_0 \nabla \phi) + q(p - n + N_D^+ - N_A^-) = 0$$

Continuity Equations

$$\begin{aligned} \frac{\partial n}{\partial t} &= \frac{1}{q} \nabla \cdot \mathbf{J}_n - (R_{nr} + R_{spont} + R_{cap}^n) & \frac{\partial n_w}{\partial t} &= \frac{1}{q} \frac{dJ_{nw}}{dx} - (R_{nr}^{qw} + R_{spont}^{qw} + R_{stim}^{qw} - R_{cap}^n) \\ \frac{\partial p}{\partial t} &= -\frac{1}{q} \nabla \cdot \mathbf{J}_p - (R_{nr} + R_{spont} + R_{cap}^p) & \frac{\partial p_w}{\partial t} &= \frac{1}{q} \frac{dJ_{pw}}{dx} - (R_{nr}^{qw} + R_{spont}^{qw} + R_{stim}^{qw} - R_{cap}^p) \end{aligned}$$

Photon Rate Equations (m modes, 1 eqn. per mode)

$$\frac{dS_m}{dt} = v_g (G_m - \alpha) S_m + \beta r_{spont}^{qw}$$

- ◆ The equations are cast into matrix form and solved simultaneously using Newton's Method.

Description of Laser Simulator



The University of
Nottingham

Optical model

- ◆ Helmholtz's scalar 2D wave equation

$$\nabla^2 \Phi + (k(x, y)^2 - \beta(\omega)^2) \Phi = 0$$

- ◆ Solved using Rayleigh quotient iteration method

Thermal model

- ◆ Lattice heat equation
- ◆ Heat sources:

- Joule heat

$$H_{Joule} = \frac{\nabla E_c}{q} \cdot \mathbf{J}_n + \frac{\nabla E_v}{q} \cdot \mathbf{J}_p$$

- Capture heat

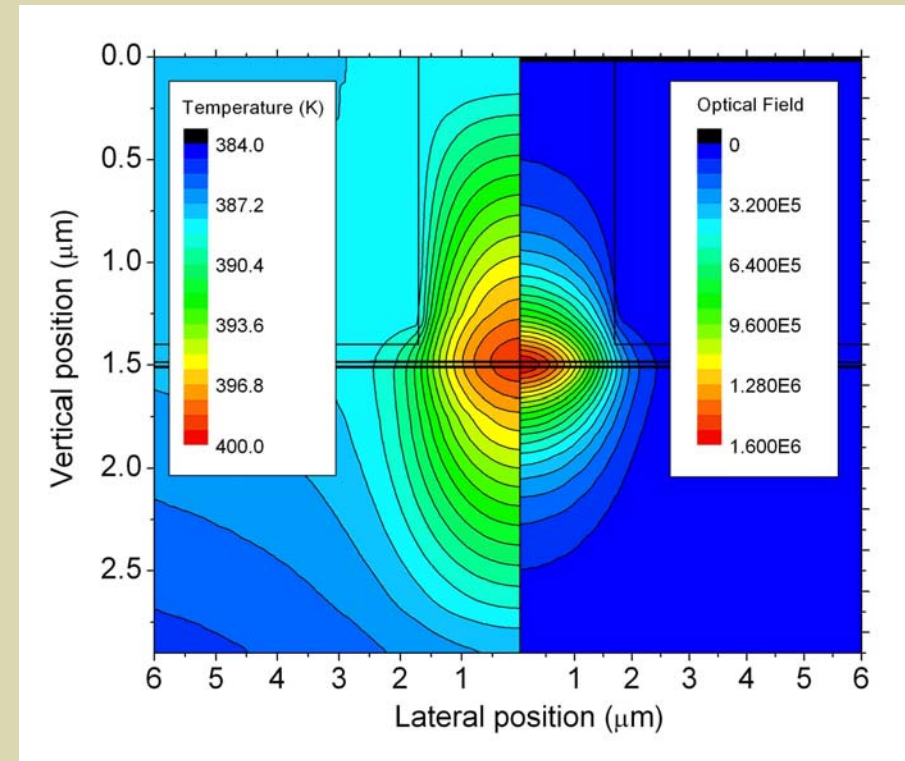
$$H_{Cap} = R_{net} \cdot (E_g - E_{gw})$$

- Recombination heat

$$H_{Recomb} = R_{nr} \cdot E_{g,w}$$

- Absorption heat

$$H_{Abs} = \sum_m v_g \alpha \Phi S_m \hbar \omega$$



Calibration of Ridge Waveguide Laser

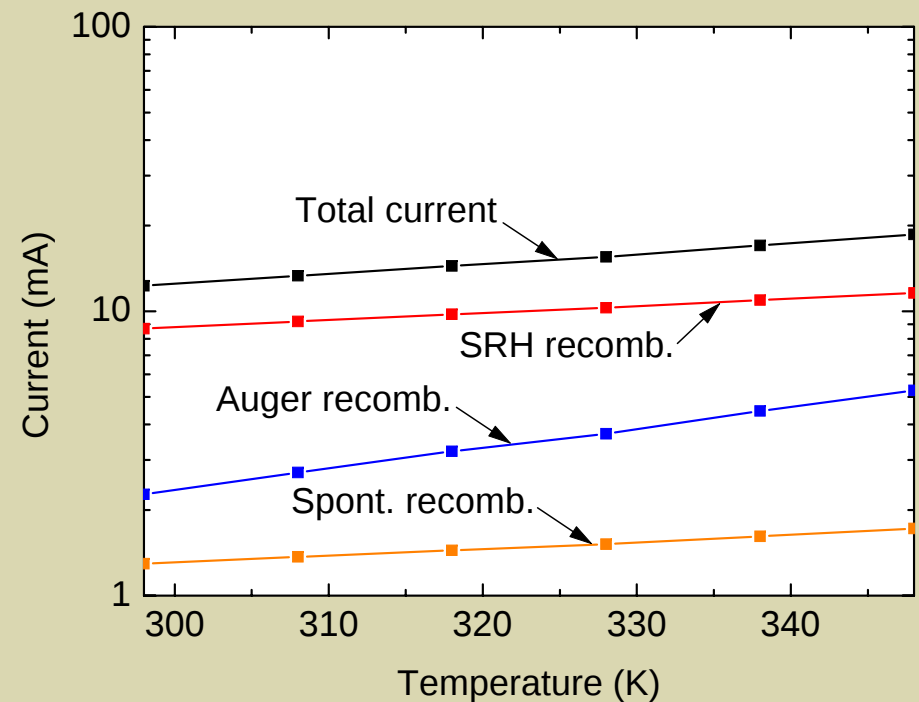
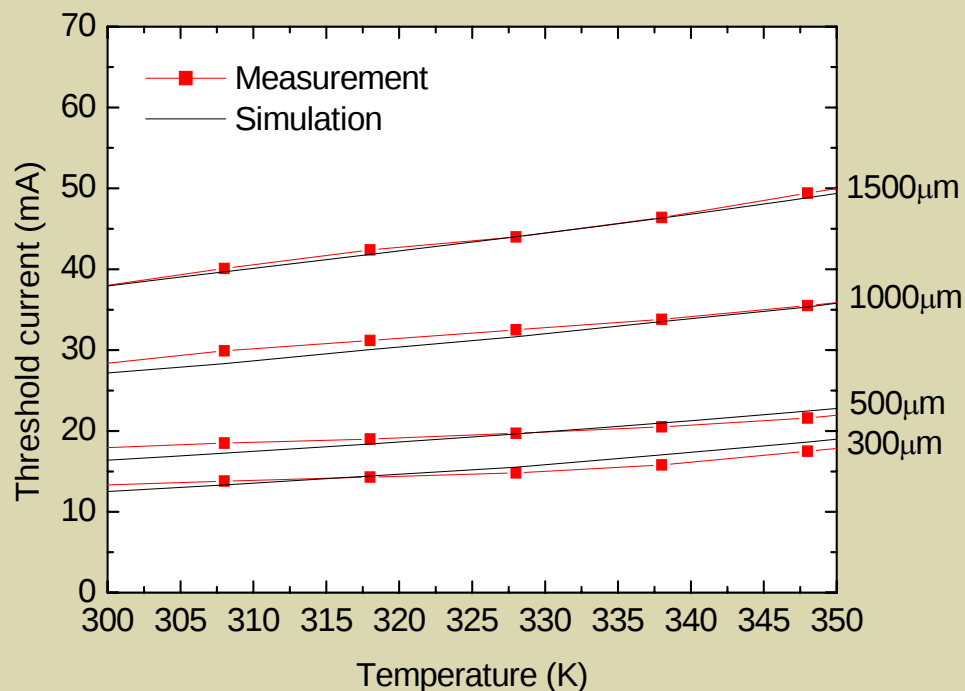
- Material parameters taken from the literature

Layer	d (μm)	E_g (eV)	μ_n (cm^2/Vs)	μ_p (cm^2/Vs)	κ (W/mK)	n_r
p-GaAs	0.10	1.42248	1309	42.2	46	3.41741
p- $\text{Al}_{0.50}\text{Ga}_{0.50}\text{As}$ (cladding)	1.00	2.08076	196	77.7	10.77	3.15105
p- $\text{Al}_{0.50-0.20}\text{Ga}_{0.50-0.80}\text{As}$ (graded)	0.16	2.08076 - 1.72303	809 - 2875	181 - 253	10.77- 14.46	3.15105 - 3.30392
$\text{Ga}_{0.61}\text{In}_{0.39}\text{N}_{0.012}\text{As}$ (QW)	0.007	1.00797	500	483	5.08	3.60
GaAs (barrier & SCL)	0.020	1.42248	7800	490	46	3.41741
n- $\text{Al}_{0.20-0.50}\text{Ga}_{0.80-0.50}\text{As}$ (graded)	0.16	1.72303 - 2.08076	2875 - 809	253 - 181	14.46- 10.77	3.30392 - 3.15105
n- $\text{Al}_{0.50}\text{Ga}_{0.50}\text{As}$ (cladding)	1.00	2.08076	196	77.7	10.77	3.15105
n-GaAs	0.30	1.42248	1851	51	46	3.41741

- Bandgap energies from Vurgaftman & Meyer, JAP 89, 5815, 2001.
- Carrier mobilities and thermal conductivities from Joachim Piprek, *Semiconductor Optoelectronic Devices*, Academic Press, 2003 & Vassil Palankovski, *Analysis and Simulation of Heterostructure Devices*, Springer, 2004.
- Refractive indices from Afromowitz, Solid State Comm., 15, 59, 1974 and from Kitatani *et al.*, Jpn. J. Appl. Phys., 37, 753, 1998 for AlGaAs and GaInNAs respectively.

Calibration of Material Parameters

- ◆ A good fit of threshold current vs temperature for different cavity lengths was achieved:
 - $\sigma_{\text{IVBA}} \sim 2 \times 10^{-16} \text{ cm}^2 \rightarrow \alpha_i = 10 \text{ cm}^{-1}$
 - $C_{\text{CHHS}} = 1 \times 10^{-28} \text{ cm}^6 \text{ s}^{-1}$
 - $\tau_n = \tau_p = 0.5 \text{ ns}$
- ◆ SRH recombination was found to dominate the threshold current.



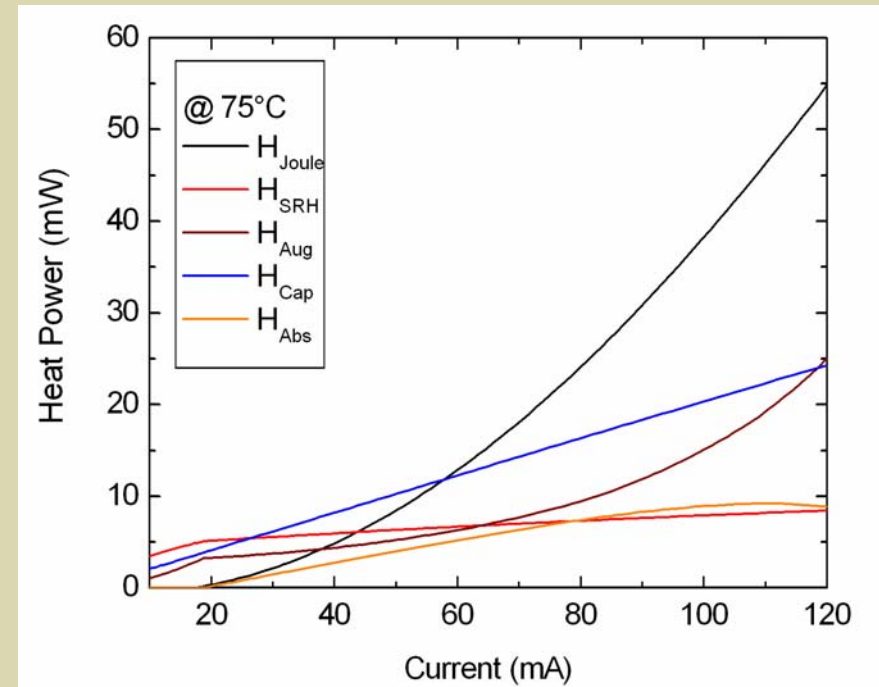
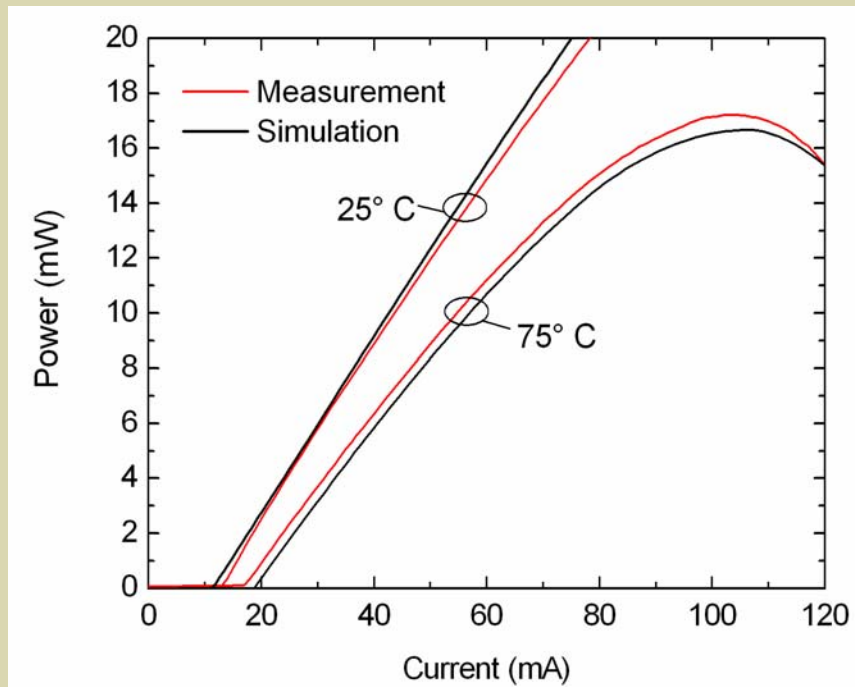
Calibration of Ridge Waveguide Laser

- ♦ $3.4 \times 300 \mu\text{m}^2$ RW laser
- ♦ To obtain agreement, Auger coefficient needs to be temperature dependent:

$$C_{\text{HSH}}(T) = C_0 \quad T < 350\text{K}$$

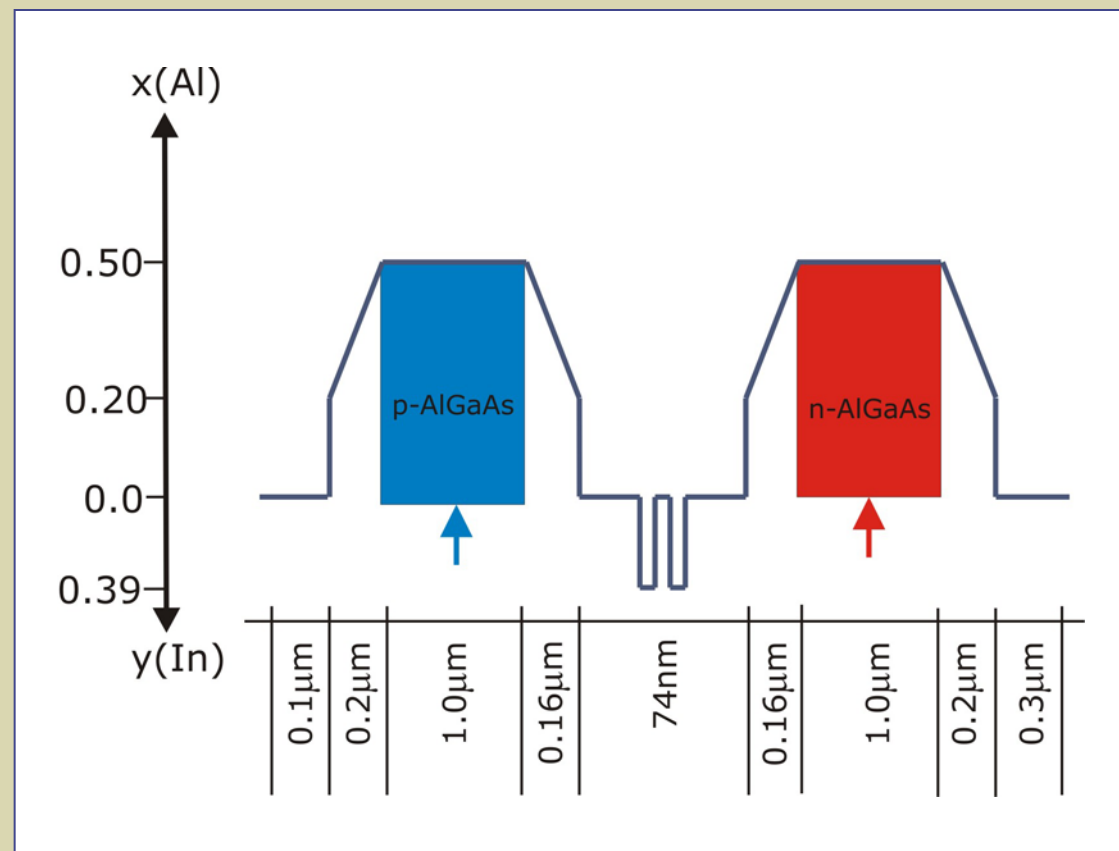
$$C_{\text{HSH}}(T) = C_0 \left[1 + \beta(T - T_0)^n \right] \quad T > 350\text{K}$$

$$C_0 = 1 \times 10^{-28} \text{ cm}^6 \text{ s}^{-1}, \beta = 5 \times 10^{-4}, n = 2.05 \text{ and } T_0 = 350 \text{ K}$$



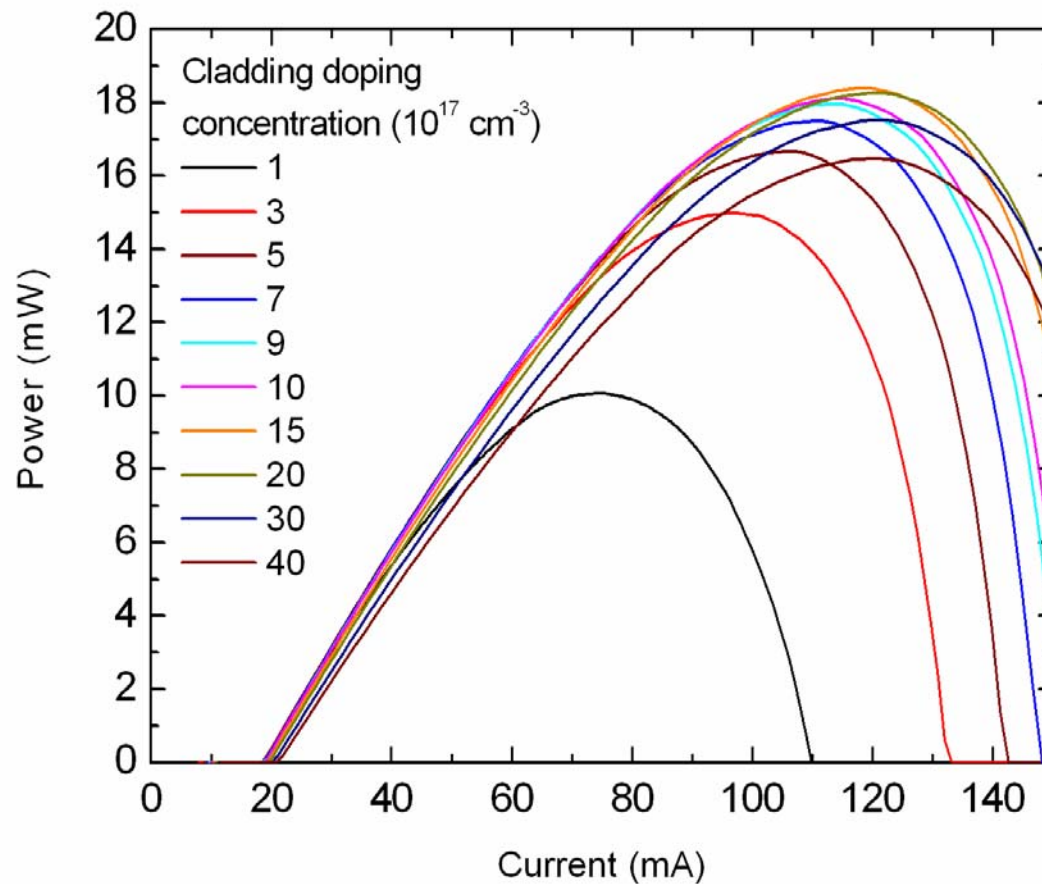
Cladding doping concentration study

- ♦ p-clad and n-clad doping concentration set equal and varied from 1×10^{17} to $4 \times 10^{18} \text{ cm}^{-3}$
- ♦ original doping concentration = $5 \times 10^{17} \text{ cm}^{-3}$



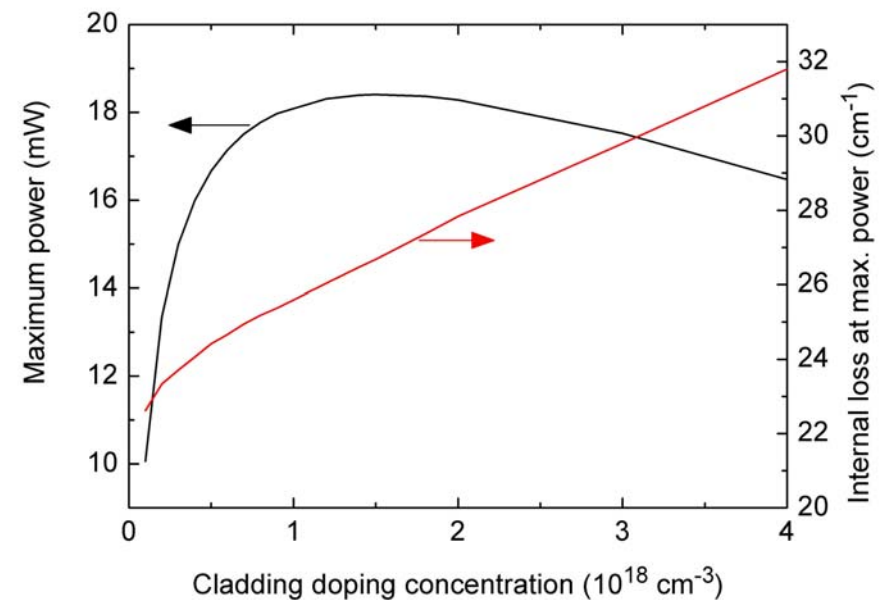
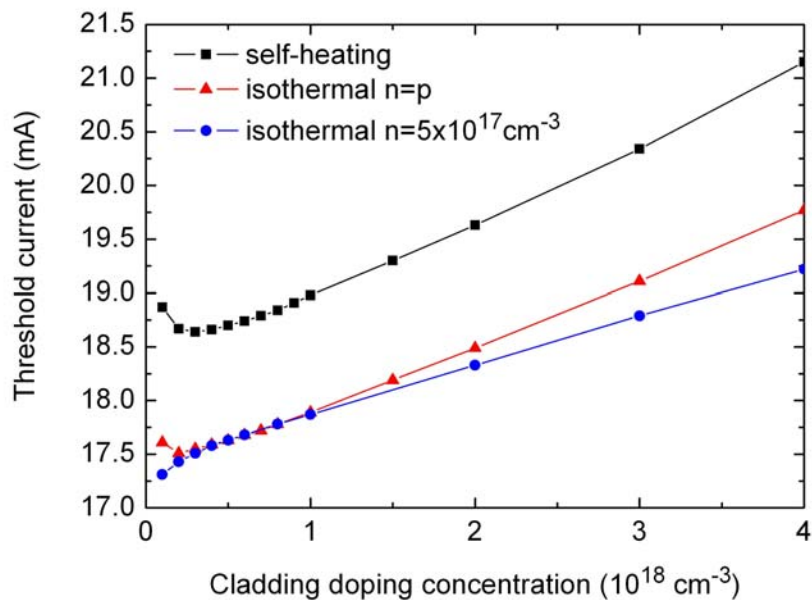
Cladding doping concentration study

- ◆ L-I curves for different cladding doping concentration at 75°C.



Cladding doping concentration study

- ◆ Threshold current vs. cladding doping concentration
- ◆ Maximum output power vs. cladding doping concentration



- ◆ 0.3% improvement in threshold current at $3 \times 10^{17} \text{ cm}^{-3}$
- ◆ 10% improvement in maximum output power at $1.5 \times 10^{18} \text{ cm}^{-3}$

- ◆ Gain and spontaneous emission calculation calibrated to experimental data.
- ◆ Auger coefficient, SRH lifetime and absorption cross section fit to obtain agreement in threshold current vs. temperature and length.
- ◆ Self-heating model and temperature dependent Auger coefficient necessary to reproduce experimental L-I curves above threshold.
- ◆ An optimum doping concentration exists to reduce heat generation due to competition between Joule heating and FCA.
- ◆ A 10% improvement in maximum output power achieved using optimum cladding doping concentration.